

W₁₈O₄₉ Nanowire Alignments with BiOCl Shell as Efficient

Photocatalyst

Zhen-Feng Huang[†], Jiajia Song[†], Lun Pan[†], Xu Jia[†], Zhe Li[†], Ji-Jun Zou^{†‡},*

Xiangwen Zhang^{†‡}, and Li Wang^{†‡}

[†]Key Laboratory for Green Chemical Technology of the Ministry of Education,

School of Chemical Engineering and Technology, Tianjin University, Tianjin 300072,

China

[‡]Collaborative Innovative Center of Chemical Science and Engineering (Tianjin),

Tianjin 300072, China.

E-mail: jj_zou@tju.edu.cn (J.-J. Zou)

Table of contents

	Captions
Table S1	Synthetic parameters of all the samples. (a, b and c: ratios defined in the starting materials, determined by ICP, and determined by XPS, respectively.)
Figure S1	XRD patterns of W@BiOCl synthesized with BiCl ₃ content increasing from W@BiOCl-1 to W@BiOCl-4.
Figure S2	UV-vis diffuse reflectance spectra of W@BiOCl with synthesized with BiCl ₃ content increasing from W@BiOCl-1 to W@BiOCl-4, pure W ₁₈ O ₄₉ and BiOCl.
Figure S3	XRD pattern of WA-3.
Figure S4	BJH pore distribution of WA-3 and WA@BiOCl-3.
Figure S5	XPS spectra of (a) W 4f, (b) Bi 4f, (c) O 1s, and (d) Cl 2p from WA@BiOCl-3.
Figure S6	UV-vis diffuse reflectance spectra of WA@BiOCl synthesized with Bi(NO ₃) ₃ content increasing from WA@BiOCl-1 to WA@BiOCl-4.
Figure S7	Changes of MO concentration with irradiated time with the presence of WA@BiOCl-3 under simulated sunlight.
Figure S8	Photoactivity of W ₁₈ O ₄₉ /BiOCl physical mixtures by mixing the individual semiconductors with composition identical to WA@BiOCl counterparts under simulated sunlight.
Figure S9	XRD patterns of WA@BiOCl-3 before and after the 5-cycling of MO degradation under simulated sunlight.

Abbreviations	WCl ₆ [g]	BiCl ₃ [g]	morphology	BET [m ² /g]	[Bi:W] ^a
BiOCl		0.236	sheet	15.1	
W@BiOCl-1	0.297	0.016	NW	51.2	1:15
W@BiOCl-2	0.297	0.03	NW	50.3	1:8
W@BiOCl-3	0.297	0.047	NW	49.1	1:5
W@BiOCl-4	0.297	0.079	NW	41.7	1:3

Abbreviations	WCl ₆ [g]	NaNO ₃ [g]	morphology	BET [m ² /g]
WA-1	0.297	0.01	alignments	56.7
WA-2	0.297	0.015	alignments	62.1
WA-3	0.297	0.02	alignments	59.4
WA-4	0.297	0.03	alignments	54.2

Abbreviations	WCl ₆ [g]	Bi(NO ₃) ₃ ·5H ₂ O [g]	morphology	BET [m ² /g]	[Bi:W]
W ₁₈ O ₄₉	0.297		NW	60	
WA@BiOCl-1	0.297	0.024	alignments	74.5	(1:15) ^[a] (6.5%) ^[b] ; (8.2%) ^[c]
WA@BiOCl-2	0.297	0.045	alignments	51.8	(1:8) ^[a] (11.1%) ^[b] ; (15.1%) ^[c]
WA@BiOCl-3	0.297	0.073	alignments	52.9	(1:5) ^[a] (19.1%) ^[b] ; (31.6%) ^[c]
WA@BiOCl-4	0.297	0.121	alignments	37.3	(1:3) ^[a] (33.7%) ^[b] ; (50.1%) ^[c]

Table S1. Synthetic parameters of all the samples. ([a], [b] and [c]: ratios defined in the starting materials, determined by ICP, and determined by XPS, respectively.)

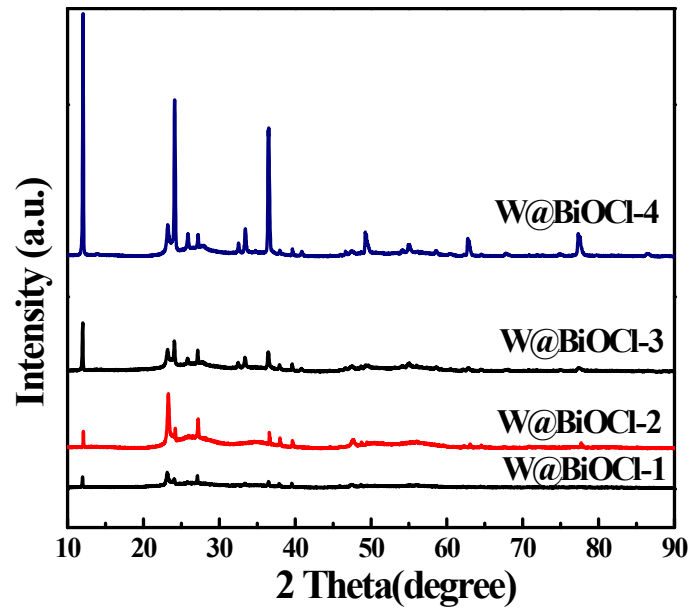


Figure S1. XRD patterns of W@BiOCl synthesized with BiCl₃ content increasing from W@BiOCl-1 to W@BiOCl-4.

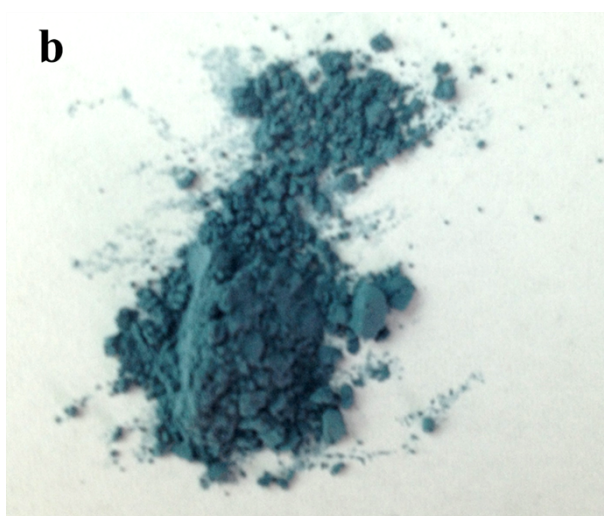
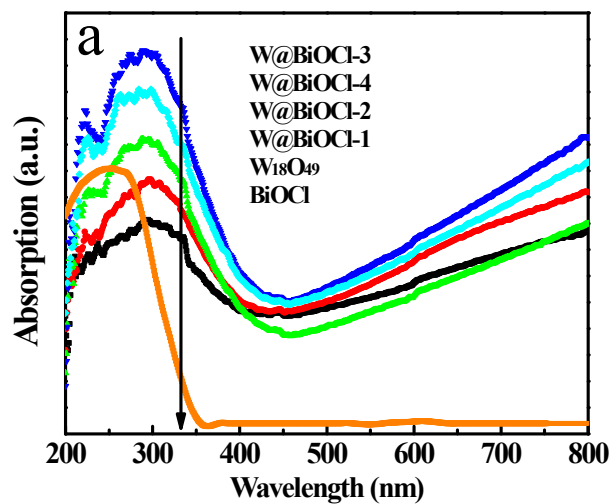


Figure S2. (a) UV-vis diffuse reflectance spectra of W@BiOCl with synthesized with BiCl₃ content increasing from W@BiOCl-1 to W@BiOCl-4, pure W₁₈O₄₉ and BiOCl, and (b) Photo image of W@BiOCl-3.

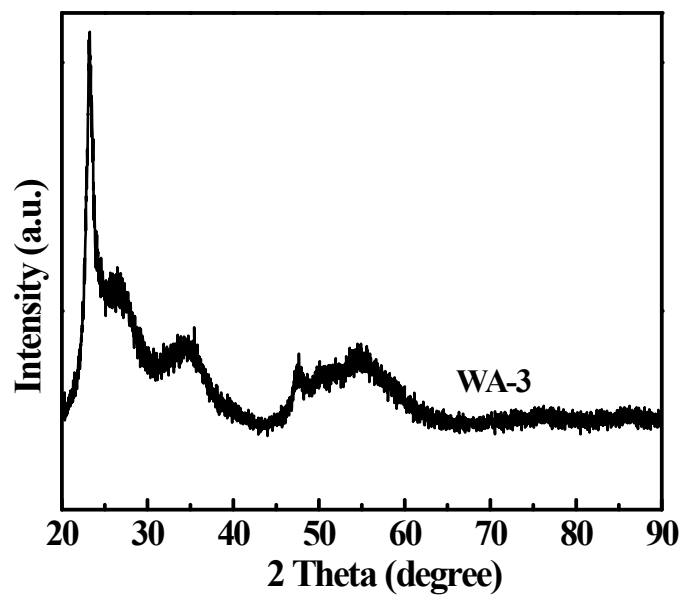


Figure S3. XRD pattern of WA-3.

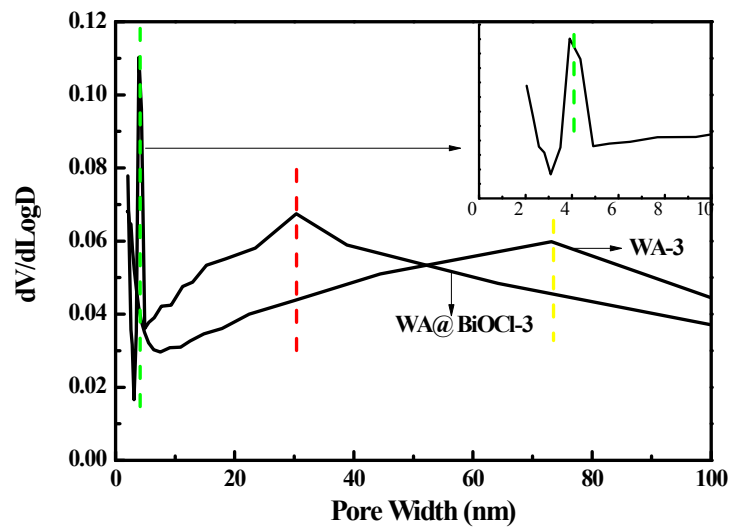


Figure S4. BJH pore distribution of WA-3 and WA@BiOCl₃.

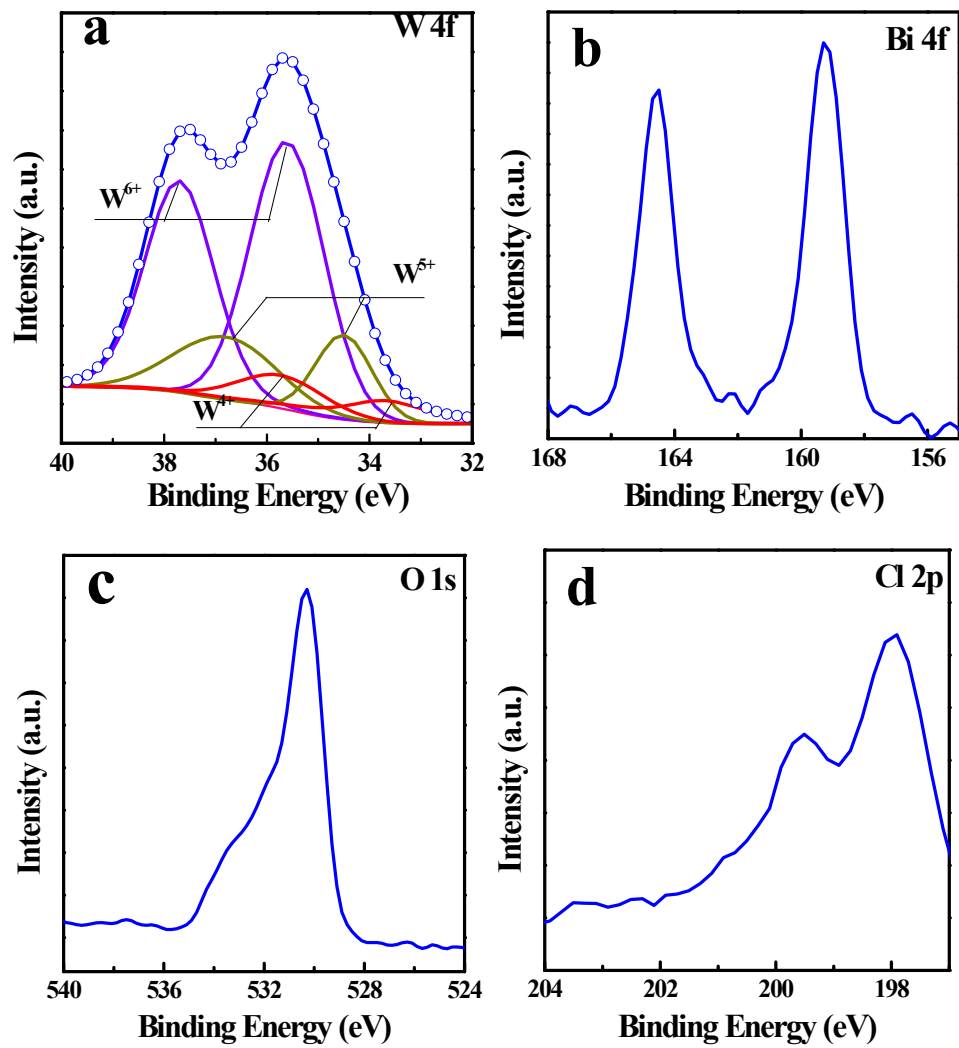


Figure S5. XPS spectra of (a) W 4f, (b) Bi 4f, (c) O 1s, and (d) Cl 2p from WA@BiOCl-3.

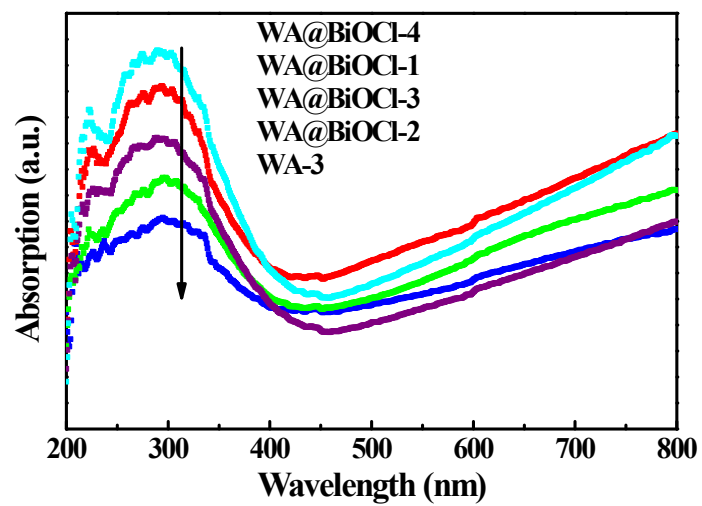


Figure S6. UV-vis diffuse reflectance spectra of WA@BiOCl synthesized with $\text{Bi}(\text{NO}_3)_3$ content increasing from WA@BiOCl-1 to WA@BiOCl-4.

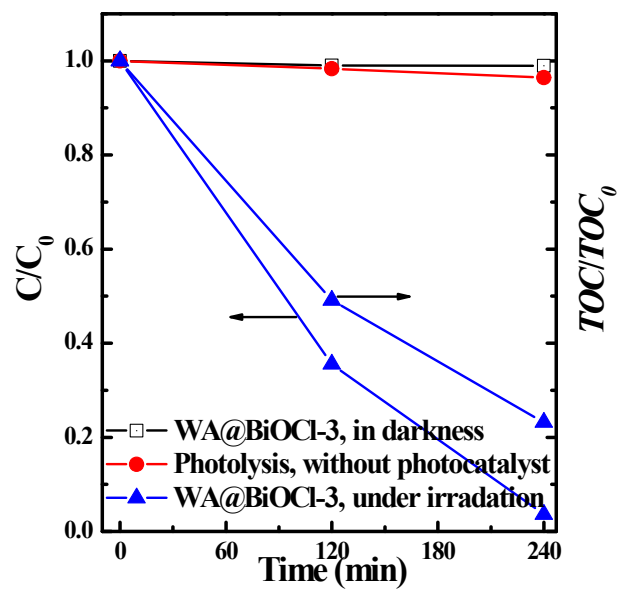


Figure S7. Changes of MO concentration with irradiated time with the presence of WA@BiOCl₃ under simulated sunlight.

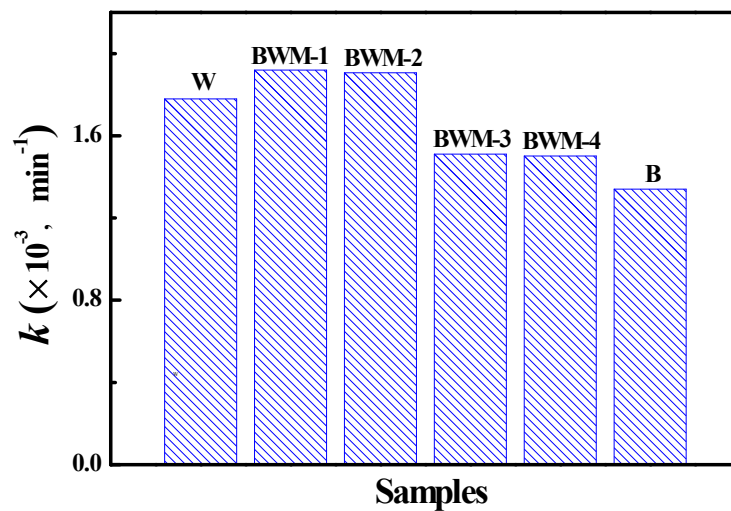


Figure S8. Photoactivity of $\text{W}_{18}\text{O}_{49}/\text{BiOCl}$ physical mixtures (BWM) by mixing the individual semiconductors with composition identical to WA@BiOCl counterparts under simulated sunlight.

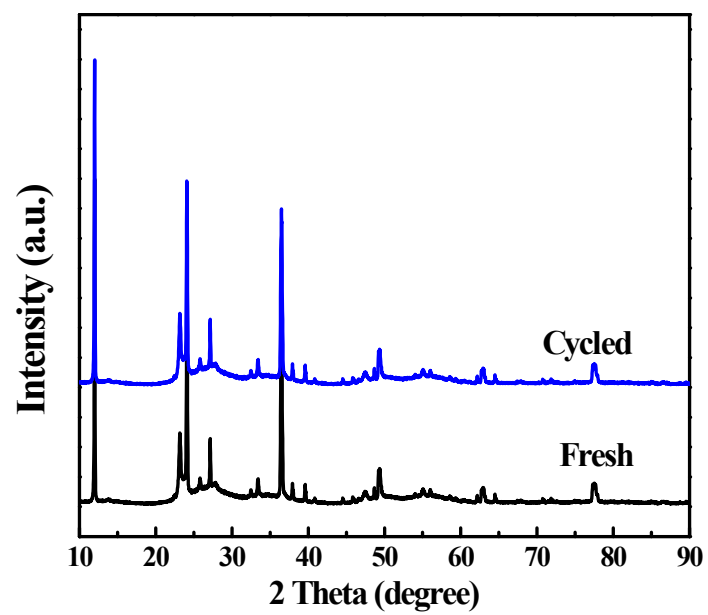


Figure S9. XRD patterns of WA@BiOCl₃ before and after the 5-cycling of MO degradation under simulated sunlight.